



PATENT

1-29-02

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Yasuhiro KOIZUMI et al

Art Unit:

S. N. 09/920,450

Examiner:

Filed: August 1, 2001

For: DEFECT INSPECTION APPARATUS
FOR PHASE SHIFT MASK

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Please make the following amendments to this application
prior to examination thereof:

In the Specification:

**Page 2, lines 8-15, delete this paragraph and substitute the
following:**

a' Phase shifter defects on such phase shift photomasks may be
generated in the mask making process. Examples of phase shifter
defects are a partially unfinished phase shifter due to adhesion
of a contamination to a region where a 180° phase shifter is to
be formed, and an excess or overetched phase shifter due to a
resist pinhole or the like present in a region where no phase
shifter should be formed.

**Page 5, lines 13-20, delete this paragraph and substitute
the following:**

q2 To attain the above-described object, the present invention
provides a defect inspection apparatus for a phase shift mask